

# Supporting Information

## Nitrogen-mediated aligned growth of hexagonal BN films for reliable high-performance InSe transistors

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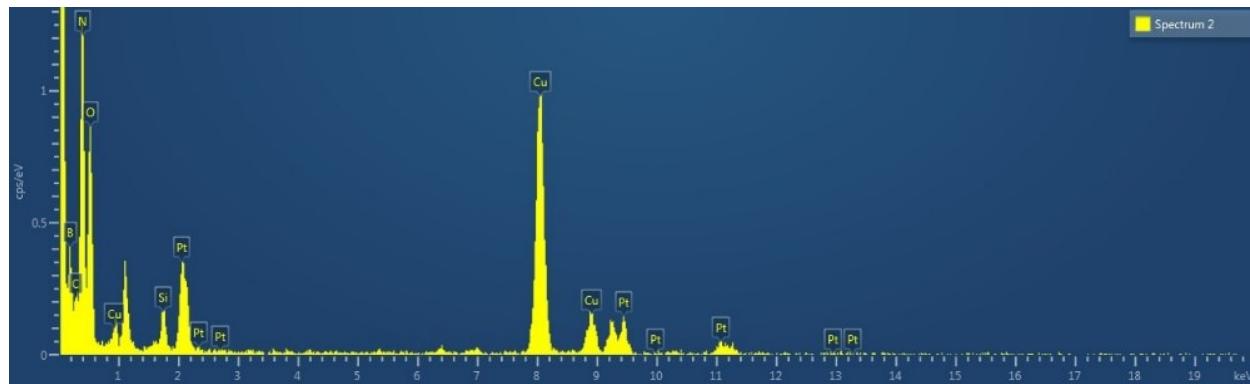
Email: mmzhu@ntu.edu.sg or htteo@ntu.edu.sg

**Table S1** Deposition conditions for the samples by HIPIMS.

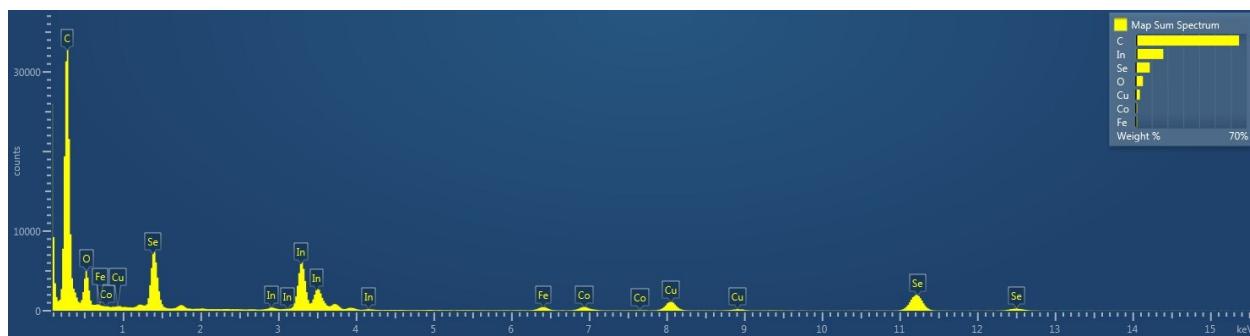
Sample Name	Gas Flow Ratio of N <sub>2</sub> /Ar (%)	Base Pressure (Torr)	Working Pressure (Torr)	Power Density (W/cm <sup>2</sup> )	Thickness (nm)
A	5	3.96 x 10 <sup>-6</sup>	3.19 x 10 <sup>-3</sup>	26.13	502.05
B	10	1.99 x 10 <sup>-6</sup>	2.58 x 10 <sup>-3</sup>	24.30	488.76
C	15	2.76 x 10 <sup>-6</sup>	1.94 x 10 <sup>-3</sup>	21.56	486.61
D	20	2.72 x 10 <sup>-6</sup>	2.14 x 10 <sup>-3</sup>	25.22	546.77
E	40	2.83 x 10 <sup>-6</sup>	2.35 x 10 <sup>-3</sup>	24.77	437.81
F	60	2.54 x 10 <sup>-6</sup>	2.84 x 10 <sup>-3</sup>	25.78	552.91
G	85	2.70 x 10 <sup>-6</sup>	3.52 x 10 <sup>-3</sup>	24.12	647.53
H	100	2.07 x 10 <sup>-6</sup>	3.79 x 10 <sup>-3</sup>	26.22	446.93

**Table S2** Summary of the peak positions of B 1s and N 1s for the samples and the difference between the peaks

Sample Name	Gas Flow Ratio of N <sub>2</sub> /Ar (%)	Peak Identification	Binding Energy (from raw data) / eV	Difference in Binding Energy between B1s and N1s / eV	Binding Energy (fitted Gaussian curves) / eV	Difference in Binding Energy between B1s and N1s (fitted Gaussian curves) / eV
A	5	B1s	190.5	206.5	190.3	206.8
		N1s	397		397.1	
B	10	B1s	189.5	207.3	189.6	207.2
		N1s	396.8		396.8	
C	15	B1s	189.6	207.4	189.8	207.1
		N1s	397		396.9	
D	20	B1s	189.8	207.2	189.8	207.2
		N1s	397		397	
E	40	B1s	189.9	207.3	189.9	207.2
		N1s	397.16		397.1	
F	60	B1s	189.7	207.6	189.7	207.5
		N1s	397.26		397.2	
G	85	B1s	189.8	207.2	189.8	207.2
		N1s	397		397	
H	100	B1s	189.8	207.2	189.8	207.1
		N1s	397		396.9	



**FIG. S1.** EDS spectrum of h-BN thin films.



**FIG. S2** EDS spectrum of InSe crystals.